



Sheet 1 of 1

PTO-1449 U.S. DEPARTMENT OF COMMERCE (Rev. 2-32) PATENT AND TRADEMARK OFFICE		ATTY. DOCKET NO: EV-2		SERIAL NO.: 10/090,465			
INFORMATION DISCLOSURE STATEMENT BY APPLICANT		APPLICANT: Livesay et al.		FILING DATE: 3/4/2002			
(Use several sheets if necessary)		GROUP: 1756		FILING DATE IF APPROPRIATE			
U.S. PATENT DOCUMENTS							
EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
Cuy	AA	2001/0016302 A1	8/23/2001	HIRAYANAGI, ET AL	430	322	
Cuy	AB	5,003,178	3/26/1991	LIVESAY	250	492.3	
	AC						
	AD						
	AE						
	AF						
	AG						
	AH						
	AI						
	AJ						
	AK						
FOREIGN PATENT DOCUMENTS							
		DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION YES NO
Cuy	AL	WO 96/36070	11/14/1996	PCT			
	AM						
	AN						
	AO						
	AP						
OTHER DOCUMENTS(Including Author, Title, Date, Pertinent Pages, etc.)							
Cuy	AQ	Olson, Kurt A., et al "Characterization, modeling and design of an electrostatic chuck with improved wafer temperature uniformity. Rev. Sci. Instrum. 66 (2) February 1995.					
Cuy	AR	Electrostatic Wafer Holder for Wafer Cooling During Reactive Ion Etching. IBM Technical Disclosure Bulletin Vol. 31, No. 1, June 1988 Armonk, New York					
	AS						
EXAMINER		DATE CONSIDERED		10/03			
Examiner: Initial if citation considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.							

FORM PTO-1449 U.S. DEPARTMENT OF COMMERCE (Rev. 2-32) PATENT AND TRADEMARK OFFICE		ATTY. DOCKET NO: EV-1		SERIAL NO.: 10/090,465				
INFORMATION DISCLOSURE STATEMENT BY APPLICANT		APPLICANT: WILLIAM R. LIVESAY, ET AL.						
(Use several sheets if necessary)		FILING DATE: 3/4/2002		GROUP: 1756				
U.S. PATENT DOCUMENTS								
EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE	
Aug	AA	6,319,655 B1	11/20/2001	WONG, ET AL.	430	311		
	AB							
	AC							
	AD							
	AE							
	AF							
	AG							
	AH							
FOREIGN PATENT DOCUMENTS								
							TRANSLATION	
		DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	YES	NO
	AI							
	AJ							
	AK							
	AL							
	AM							
	AN							
	AO							
OTHER DOCUMENTS(Including Author, Title, Date, Pertinent Pages, etc.)								
Aug	AP	"Synthesis of Siloxanes and Silsesquioxanes for 157 nm Microlithography", Hounq V. Tran, et al. Polymeric Materials: Science & Engineering 2001, 84, xxx.						
Aug	AQ	"Electron Beam Processing of Deep-UV Resist", M.F. Ross, et al. Pages 02-19						
Aug	AR	"157 nm Resist Materials: Progress Report", Colin Brodsky, et al. Dept. of Chemistry and Chemical Engineering, The University of Texas at Austin, Austin, Texas 78735. Pages 3396-3401						
Aug	AS	"E-Beam Stabilization of ArF (193nm) Photoresist for Implementation of Sub-100nm Devices", Cha-Won Koh, et al. Memory R&D Division, Hynix Semiconductor, Inc., Pages 02-11.						
Aug	AT	"Organic Imaging Materials: A View of the Future", Michael D. Stewart, et al. Journal of Physical Organic Chemistry, J. Phys. Org. Chem. 2000; 13: 767-774						
EXAMINER		DATE CONSIDERED			10/03			
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